SUPPLEMENTARY INFORMATION

Stabilizing Perovskite Quantum Dot Oxygen Sensors through Ultra-Long 2 mm Horizontally Aligned Nanopores in Anodic Alumina Oxide Templates

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Fig. S1 FAPbBr₃ quantum dots dispersed in octane.



Fig. S2 Photographs of samples showing glass with deposited PQDs (PQDs-glass), HAAO alone, and HAAO with embedded PQDs (PQDs-HAAO). The PQDs used in this study are FAPbBr₃ quantum dots.



Fig. S3 Current density–time transient during hard anodization process in 0.3 M H₂SO₄. The inset shows SEM images of a typical HAAO film. The scale bars in the SEM images are 200 nm.



Fig. S4 SEM image of FAPbBr₃ quantum dots.



Fig. S5 The QY characteristics of PQDs with different substrates. (A) Excitation and (B) emission spectra. (C) The changes of QY after stored in oxygen-enriched atmosphere (~20% oxygen) for 1 hour.



Fig. S6 Response of the sensor to different gases of oxygen (100%), ammonia (1000 ppm), and nitric oxide of (1000 ppm).



Fig. S7 Five cycles of response and recovery obtained by repetitively switching between 100% O_2 and 100% N_2 for (A) PQDs-glass and (B) PQDs-HAAO sensors.

Parameters	PQDs-glass	PQDs-HAAO		
Equation	$\frac{I_0}{I} = 1 + (K_D + K_s)$	$(Q]) + K_D K_S [Q]^2$		
Ks	-0.00499 ± 0.00032	-0.00396 ± 0.00018		
K _D	0.0668 ± 0.00356	0.04196 ± 0.00117		
Reduced Chi-Square	0.01401	0.00133		
R-Square	0.99065	0.99841		

 Table S1. Summary of fitting results using second order Stern-Volmer plot.

Gas sensor	Gas type	Response time (s)	Recovery time (s)	Long-term Stability (hours)	References
FAPbI ₃	NO ₂	2	22	72	Ref. ¹
CsPbBr ₃ QDs	H_2S	278	730	216	Ref. ²
MAPbBr ₃	NH_3	7	73	NA	Ref. ³
MAPbBr ₃ QDs	$\rm NH_3$	1000	1000	NA	Ref. ⁴
MAPbBr ₃ -TBA	$\rm NH_3$	61	65	NA	Ref.⁵
CsPbBr ₃	NH_3	8	780	96	Ref. ⁶
FAPbBr ₃ QDs-HAAO	0 ₂	83.9	113.3	504	This work

Table S2. Comparison of the current work and previously reported fluorescent perovskite-based sensors.

 Table S3.
 Detail-fitted parameters of the TRPL decay curves for Fig. 7.

Sample	A ₁	$ au_1$ (ns)	A ₂	$ au_2$ (ns)	A ₃	$ au_3$ (ns)	$ au_{avg}$ (ns)
PQDs-glass fresh	0.25	9.04	0.38	53.69	0.37	188.63	154.35
PQDs-glass after 2 weeks	0.58	3.24	0.39	10.65	0.03	37.94	13.12
PQDs-HAAO fresh	0.36	9.39	0.45	46.06	0.18	140.05	91.85
PQDs-HAAO after 2 weeks	0.41	9.19	0.42	38.52	0.16	121.88	77.03

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